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				Application Number	10/597,199-Conf. #7625	
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STATEMENT BY APPLICANT				First Named Inventor	Karsten Buse	
				Art Unit	N/A 1792	
	(Use as many sh	eets a:	necessary)	Examiner Name	Not Yet Assigned Hiteshew	
Sheet	1	of	1	Attorney Docket Number	20811/0204481-US0	

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		Country Code ³ -Number ⁴ -Kind Code ⁶ (# known)	Date MM-DD-YYYY	Applicant of Cited Document			
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	NON PATENT LITERATURE DOCUMENTS					
Examiner Initials	Cite No.1	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	1.5			
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I - VOILINIOI	/Felisa Hiteshew/	Date	01/18/2008
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